

providing a substrate that is at least partially covered by a layer of radiation-sensitive material;

providing a vacuum to a first vacuum chamber;

providing utilities through conduits to at least one component moveable in at least a first direction in said first vacuum chamber;

projecting a projection beam of radiation using a radiation system through said vacuum chamber;

using patterning structure to endow the projection beam with a pattern in its cross-section;

projecting the patterned projection beam of radiation onto a target portion of the layer of radiation-sensitive material,

characterized in that the method comprises the steps of:

shielding said vacuum in said vacuum chamber with a conduit shield from said conduits,

moving said conduit shield so as to follow the moveable component; and

providing a second vacuum in a space comprising the conduits and separated by the conduit shield from said vacuum chamber.

At page 10, delete paragraph [0039] and replace it with the following new paragraph:

[0039] Figure 1 schematically depicts a lithographic projection apparatus 1 according to the invention. The apparatus comprises:

- a radiation system LA, IL for supplying a projection beam PB of radiation (e.g. UV or EUV radiation, electrons or ions);
- a first object table (mask table) MT provided with a first object (mask) holder for holding a mask MA (e.g. a reticle), and connected to first positioning means PM for accurately positioning the mask with respect to item PL;
- a second object table (substrate table) W2T provided with a second object (substrate) holder for holding a substrate W2 (e.g. a resist-coated silicon wafer), and connected to second positioning means P2W for accurately positioning the substrate with respect to item PL;
- a third object table (substrate table) W3T provided with a third object (substrate) holder for holding a substrate W3 (e.g. a resist-coated silicon wafer), and connected

to third positioning means P3W for accurately positioning the substrate with respect to item PL; and

- Q3
Cont
- a projection system ("lens") PL (e.g. a refractive or catadioptric system, a mirror group or an array of field deflectors) for imaging an irradiated portion of the mask MA onto a target portion C of the substrate W2, W3.

At page 15, delete paragraph [0055] and replace it with the following new paragraph:

ay

[0055] A "swap" operation, in which the second object table 130 moves from one of the exposure 200 and measuring 300 areas to the other area and the third object table W3T moves in the opposite direction, is depicted schematically in Figures 4 and 5. Although Figures 4 and 5 illustrate one combination of movements which result in so-called "swap", the sequence of movements could be in a different order.

At page 15, delete paragraph [0056] and replace it with the following new paragraph:

Q5

[0056] As shown in Figure 4, if swap is to be initiated, the first step is the translation of the second joint 105, 155 of both first and second conduit conducts. In the case of the second object table W2T, the second joint 105 of the first conduit conduct 100 moves from its second position 102 to a first position 101 which is positioned closer to the exposure area 200 than to the measuring area 300. During this operation, the second object table W2T remains substantially within the measuring area 300 and it may move within that area. In the case of the third object table W3T, the second joint 155 of the second conduit conduct 150 moves from the first position 151 to a second position 152 while the third object table W3T remains substantially on the exposure area 200.

See the attached Appendix for the changes made to effect the above paragraphs.

IN THE CLAIMS:

Please enter the following amended claims:

- Q6
1. (Amended) A lithographic projection apparatus comprising:
 - a radiation system to provide a projection beam of radiation;
 - a first object table adapted to support patterning structure which can be used to pattern the projection beam according to a desired pattern;